Specifications

MECAPOL P 400

- High capacity polishing machine.
- Base plate Ø 380 mm. • Almag plate Ø 400 mm x 20 mm,
- easily removable. • Variable speed 30 to 300 Rpm.
- Constant torque.
- Progressive acceleration.
- 2 pre-selected speed 50/100 Rpm.
- 2 direction rotation.
- Power 750 Watts.
- Digital display of speeds.
- Touch sensitive keys with LED indicators.
- · Frame protected against rust corrosion.
- · Painted steel body.
- Large proportional bowl, tilted and removable.
- Water inlet driven by sluice gate.
- Multi spray water cooling.
- Voltage 230 V., single phase

PE.RE B

- Polishing head with central pressure.
- Digital display of time and pressure.
- · Low pressure loading and unloading.
- Touch sensitive keys.
- · Adjustable sweep (position, amplitude and velocity).
- Tank for 150 ml of lubricant.
- Adjustable and driven lubricant flow.
- Consolidated spindle for intensive use.
- Power 120 Watts.
- Variable speed 20 to 80 Rpm.
- Pneumatic pressure adjusted electronically from 0,5 to 40 daN.
- Direct reading of pressure.
- Voltage 230 V., single phase.





Polishing machine for substrates

Operating

The MECAPOL P 400 can be used to prepare substrates of Ø 2 to 6".

- This machine has been designed for standard polishing as well as CPM applications.
- Due to quick changing of its wafer holder and its polishing plate, this polishing machine is very well adapted to development and laboratories applications.
- As speed, load and time are adjustable, all processes can be achieved.

Width: 1000 mm Depth: 755 mm Height: 160/590 mm Weight: 145 kg.

Accessories

- Almag plate Ø 400 x 20 mm.
- 57112 Smooth specimen holder Ø 210.
- 57165 Slurry dispenser Distridiam.



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jinette by atlantic. Photos : Patrick Avavian. Avril 2006

POLISHING